

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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APPLICANT
Yoshiki NISHIBAYASHI, et al.

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GROUP
1763

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
<i>AWO</i>		US 6,184,611	02/06/2001	Saito et al.	
<i>AWO</i>		US 6,439,986	08/27/2002	Myoung et al.	
<i>AWO</i>		US 6,213,856 B1	04/10/2001	Cho et al.	
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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
<i>AWO</i>		K. Okano, "Mold growth of polycrystalline pyramidal-shape daimond for field emitters", Diamond and Related Materials 5, (1996), pp. 19-24.
<i>AWO</i>		Hiroshi Shiomi, "HIGH-RATE REACTIVE ETCHING OF DIAMOND AND FABRICATION OF POROUS DIAMOND FOR FIELD-EMISSION CATHODE", NEW DIAMOND, Vol. 13, No. 4, pp. 28-29.
<i>AWO</i>		W.P. Kang, et al., "Micropatterned polycrystalline diamond field emittter vacuum diode arrays", J.Vac. Sci Technol. B 14(3), May/Jun 1996, pp. 2068-2071.

EXAMINER

Alan Olson

DATE CONSIDERED

12-6-2004

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